

ABSTRACT

A method for forming a zirconium compound film on a substrate by a sputtering process using a zirconium target which contains a metal (such as tin or zinc) 5 of which the sputtering yield in an argon atmosphere is more than twice that of zirconium in place of a conventional metallic zirconium target. An article coated with the zirconium compound film and a sputtering target used for coating the film are provided. It is desirable that the content of the metal be 1 - 45 at%, but a third metal can be added thereto.

10